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PATENT
8007-1118**IN THE U.S. PATENT AND TRADEMARK OFFICE**

Applicants: HOSOKAWA et al. Confirmation: 6310
Serial No.: 10/594,567 Art Unit: Not assigned
Filed: September 27, 2006 Examiner: Not assigned
For: MATERIAL FOR CHEMICAL VAPOR DEPOSITION
AND THIN FILM FORMING METHOD

INFORMATION DISCLOSURE STATEMENT

Assistant Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

December 27, 2006

Sir:

In compliance with Rules 1.97 and 1.98, and in fulfillment of the duty of disclosure under Rule 1.56, included with the attached Form PTO-1449 are references discussed in the present specification, which are hereby made of record in the above-identified application. An English language abstract is provided for each document. Together, the discussion in the specification and accompanying abstracts satisfy the requirement for a concise explanation of relevance.

This Information Disclosure Statement is being submitted within three months of the filing date of the present application; therefore, no fee is required. The Examiner is courteously requested to initial and return a copy of the accompanying Form PTO-1449 to confirm entry into the record and consideration of the listed references.

Respectfully submitted,

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RJP:rk



(Use several sheets if necessary)

8007-1118

10/594.567

HOSOKAWA et al.

September 27, 2006

2812

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
	09-121027	05-06-1997	JAPAN			*	
	09-302471	11-25-1997	JAPAN			*	
	2002-053504	02-19-2002	JAPAN			*	
	2002-053960	02-19-2002	JAPAN			*	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

[illegible]

EXAMINER:

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.

* English language abstract provided for the Examiner's convenience

RJP:rk